

	L #	Hits	Search Text	DBs	Time Stamp
1	L1	65	("20020001973" "20020016085" " "20020034626" "2002006434" 1" "20020106500" "200201232" 40" "20020141024" "20020192" 980" "20030064607" "2003011" 9307" "20030157248" "200301" 98895" "20040069410" "20040" 096586" "20040096593" "2004" 0096672" "20040099952" "200" 40101633" "20040102031" "20" 040161532" "20040170760" "2" 0040185679" "20050064698" " " 4357451" "4882008" "4885262" " "5504042" "5686054" "5700" 844" "5789027" "5849640" "5" 851715" "5858457" "5920790" "6140252" "6171661" "61773" 29" "6232658" "6258735" "62" 68276" "6268288" "6270846" " " "6271273" "6312793" "632901" 7" "6329062" "6340628" "636" 5266" "6383466" "6383955" " " 6386466" "6387453" "6391932" " "6392017" "6420441" "6444" 715" "6455417" "6479374" "6" 500770" "6548113" "6558755" "6573030" "6576300" "65763" 45" "6596467" "6596654" "66" 10362" "6632478" "6667147" " " "6677251" "6715498" "675608" 5" "6759098" "6797643" "680" 5801" "6812043" "6815373" " " 6831284" "6846380" "6848458" " "6849549" "6867086" "6903" 004" "6914014" "7018918" "7" 094713" "7166531" "7176144" ).PN.	USPAT	2007/11/23 19:14
2	L2	1	L1 and (plasma same ((HF same LF) (dual duel)adj frequency (low adj frequency same high adj frequency)))	USPAT	2007/11/23 19:14

on Hotel Computer  
10/807,680

2

3  
L6

3	L3	22	(porous near5 dielectric) and (plasma same ((HF same LF) (dual duel)adj frequency (low adj frequeny same high adj frequency)))	USPAT	2007/11/23 19:14
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X

	L #	Hits	Search Text	DBs	Time Stamp
4	L4	88	( "20020001973"   "20020016085" "   "20020034626"   "2002006434" 1"   "20020106500"   "200201232" 40"   "20020141024"   "20020192" 980"   "20030064607"   "2003011" 9307"   "20030157248"   "200301" 98895"   "20040069410"   "20040" 096586"   "20040096593"   "2004" 0096672"   "20040099952"   "200" 40101633"   "20040102031"   "20" 040161532"   "20040170760"   "2" 0040185679"   "20050064698"   " 4357451"   "4882008"   "4885262" "   "5504042"   "5686054"   "5700" 844"   "5789027"   "5849640"   "5" 851715"   "5858457"   "5920790"   "6140252"   "6171661"   "61773" 29"   "6232658"   "6258735"   "62" 68276"   "6268288"   "6270846"   " "6271273"   "6312793"   "632901" 7"   "6329062"   "6340628"   "636" 5266"   "6383466"   "6383955"   " 6386466"   "6387453"   "6391932" "   "6392017"   "6420441"   "6444" 715"   "6455417"   "6479374"   "6" 500770"   "6548113"   "6558755"   "6573030"   "6576300"   "65763" 45"   "6596467"   "6596654"   "66" 10362"   "6632478"   "6667147"   " "6677251"   "6715498"   "675608" 5"   "6759098"   "6797643"   "680" 5801"   "6812043"   "6815373"   " 6831284"   "6846380"   "6848458" "   "6849549"   "6867086"   "6903" 004"   "6914014"   "7018918"   "7" 094713"   "7166531"   "7176144" ).PN.	US-PGPUB; USPAT; USOCR	2007/11/23 19:14
5	L5	1	L1 and (plasma same ((HF same LF)(dual duel)adj frequency (low adj frequeny same high adj frequency)))	US-PGPUB; USPAT; USOCR	2007/11/23 19:15

4

6	L6	65	(porous near5 dielectric) and (plasma same ((HF same LF)(dual duel)adj frequency (low adj frequeny same high adj frequency)))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	2007/11/23 19:15 .
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5

	L #	Hits	Search Text	DBs	Time Stamp
7	L7	1	L1 and (plasma same ((HF same LF) (dual duel)adj frequency (low adj frequeny same high adj frequency)))	US-PGPUB; USPAT; USOCR	2007/11/23 19:15

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Date: 11/23/2007

Time: 18:12:10

 **PALM INTRANET**

## Inventor Information for 10/807680

Inventor Name	City	State/Country
WU, QINGGUO	TUALATIN	OREGON
FU, HAIYING	WEST LINN	OREGON
MUIR, TIMOTHY J.	TIGARD	OREGON

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## Inventor Name Search Result

Your Search was:

Last Name = WU

First Name = QINGGUO

Application#	Patent#	Status	Date Filed	Title	Inventor Name
10624959	7112615	150	07/22/2003	POROUS MATERIAL FORMATION BY CHEMICAL VAPOR DEPOSITION ONTO COLLOIDAL CRYSTAL TEMPLATES	WU, QINGGUO
10672311 IDS	7208389	150	09/26/2003	METHOD OF POROGEN REMOVAL FROM POROUS LOW-K FILMS USING UV RADIATION	WU, QINGGUO
10789103 IDS	Not Issued	41	02/27/2004	Methods for producing low-k CDO films with low residual stress	WU, QINGGUO
10800409 IDS	Not Issued	100	03/11/2004	METHODS FOR PRODUCING LOW-K CDO FILMS	WU, QINGGUO
10807680	Not Issued	30	03/23/2004	Methods of porogen removal for porous low dielectric constant films using plasma treatments	WU, QINGGUO
10820525 IDS	Not Issued	41	04/07/2004	Methods for producing low-k CDO films with low residual stress	WU, QINGGUO
10849568 IDS	Not Issued	71	05/18/2004	Method for improving mechanical properties of low dielectric constant materials	WU, QINGGUO
10927777 IDS	7241704	150	08/27/2004	METHODS FOR PRODUCING LOW STRESS POROUS LOW-K DIELECTRIC MATERIALS USING PRECURSORS WITH ORGANIC FUNCTIONAL GROUPS	WU, QINGGUO
10941502 IDS	Not Issued	99	09/14/2004	METHODS FOR IMPROVING INTEGRATION PERFORMANCE OF LOW STRESS CDO FILMS	WU, QINGGUO

<u>11369658</u> IDS	Not Issued	30	03/06/2006	Methods for fabricating high hardness/modulus low dielectric constant materials	WU, QINGGUO
<u>11608056</u> IDS	Not Issued	30	12/07/2006	PECVD METHODS FOR PRODUCING ULTRA LOW-K DIELECTRIC FILMS USING UV TREATMENT	WU, QINGGUO
<u>11693661</u> IDS	Not Issued	30	03/29/2007	METHODS FOR IMPROVING PERFORMANCE OF ODC FILM WITH DIELECTRIC CONSTANT < 4.0	WU, QINGGUO
<u>11764750</u>	Not Issued	41	06/18/2007	METHODS FOR PRODUCING LOW STRESS POROUS LOW-K DIELECTRIC MATERIALS USING PRECURSORS WITH ORGANIC FUNCTIONAL GROUPS	WU, QINGGUO
<u>11936752</u> dep. meth ch 34 not publ	Not Issued	19	01/01/0001	METHODS FOR IMPROVING INTEGRATION PERFORMANCE OF LOW STRESS CDO FILMS	WU, QINGGUO
<u>11936754</u>	Not Issued	19	01/01/0001	METHODS FOR PRODUCING LOW-K CDO FILMS	WU, QINGGUO
<u>60397747</u>	Not Issued	159	07/22/2002	Chemical vapor deposition onto colloidal crystal templates	WU, QINGGUO
<u>60524330</u>	Not Issued	159	11/20/2003	Methods for producing low-k CDO film of low residue stress with dielectric constant < 3.0	WU, QINGGUO
<u>60852635</u>	Not Issued	160	10/17/2006	PECVD method for producing ultra low-k dielectric films using UV treatment	WU, QINGGUO
<u>60949204</u>	Not Issued	20	07/11/2007	METHODS FOR FABRICATING ZEOLITE NANO-CRYSTAL BASED LOW-K DIELECTRIC FILMS CONTAINING Si(CxHy)n GROUPS AND TREATING FILMS BY ULTRA-VIOLET THERMAL PROCESSING	WU, QINGGUO

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## Inventor Name Search Result

Your Search was:

Last Name = FU

First Name = HAIYING

Application#	Patent#	Status	Date Filed	Title	Inventor Name
10099232	6764952	150	03/13/2002	SYSTEMS AND METHODS TO RETARD COPPER DIFFUSION AND IMPROVE FILM ADHESION FOR A DIELECTRIC BARRIER ON COPPER	FU, HAIYING
10184681 2003017081D	6777349	150	06/28/2002	HERMETIC SILICON CARBIDE	FU, HAIYING
10334350 -duo pro	6855645	150	12/30/2002	SILICON CARBIDE HAVING LOW DIELECTRIC CONSTANT	FU, HAIYING
10672311 IPS	7208389	150	09/26/2003	METHOD OF POROGEN REMOVAL FROM POROUS LOW-K FILMS USING UV RADIATION	FU, HAIYING
10789103 IPS	Not Issued	41	02/27/2004	Methods for producing low-k CDO films with low residual stress	FU, HAIYING
10800409 IPS	Not Issued	100	03/11/2004	METHODS FOR PRODUCING LOW-K CDO FILMS	FU, HAIYING
10807680	Not Issued	30	03/23/2004	Methods of porogen removal for porous low dielectric constant films using plasma treatments	FU, HAIYING
10820525 IPS	Not Issued	41	04/07/2004	Methods for producing low-k CDO films with low residual stress	FU, HAIYING
10825888 IPS	7253125	150	04/16/2004	METHOD TO IMPROVE MECHANICAL STRENGTH OF LOW-K DIELECTRIC FILM USING MODULATED UV EXPOSURE	FU, HAIYING
10860340 IPS	7094713	150	06/02/2004	METHODS FOR IMPROVING THE CRACKING RESISTANCE	FU, HAIYING

				OF LOW-K DIELECTRIC MATERIALS	
10869474	7282438	150	06/15/2004 ND	LOW-K SIC COPPER DIFFUSION BARRIER FILMS	FU, HAIYING
10927777 IDS	7241704	150	08/27/2004	METHODS FOR PRODUCING LOW STRESS POROUS LOW-K DIELECTRIC MATERIALS USING PRECURSORS WITH ORGANIC FUNCTIONAL GROUPS	FU, HAIYING
10941502 IDS	Not Issued	99	09/14/2004	METHODS FOR IMPROVING INTEGRATION PERFORMANCE OF LOW STRESS CDO FILMS	FU, HAIYING
10982654 IDS	Not Issued	30	11/05/2004	Methods of improving porogen removal and film mechanical strength in producing ultra low-k carbon doped oxide films using radical photopolymerization	FU, HAIYING
11369658 FOS	Not Issued	30	03/06/2006	Methods for fabricating high hardness/modulus low dielectric constant materials	FU, HAIYING
11376510	Not Issued	93	03/14/2006	METHODS FOR IMPROVING THE CRACKING RESISTANCE OF LOW-K DIELECTRIC MATERIALS	FU, HAIYING
11693661 IDS	Not Issued	30	03/29/2007	METHODS FOR IMPROVING PERFORMANCE OF ODC FILM WITH DIELECTRIC CONSTANT < 4.0	FU, HAIYING
11764750	Not Issued	41	06/18/2007	METHODS FOR PRODUCING LOW STRESS POROUS LOW-K DIELECTRIC MATERIALS USING PRECURSORS WITH ORGANIC FUNCTIONAL GROUPS	FU, HAIYING
11824049	Not Issued	30	06/28/2007	Method to improve mechanical strength of low-K dielectric film using modulated UV exposure	FU, HAIYING
11893490	Not Issued	25	08/15/2007 ?	Low-k sic copper diffusion barrier films	FU, HAIYING
11936752	Not Issued	19	01/01/0001	METHODS FOR IMPROVING INTEGRATION PERFORMANCE OF LOW STRESS CDO FILMS	FU, HAIYING
11936754	Not	19	01/01/0001	METHODS FOR PRODUCING	FU, HAIYING

60524330

	Issued			LOW-K CDO FILMS	
60524330	Not Issued	159	11/20/2003	Methods for producing low-k CDO film of low residue stress with dielectric constant < 3.0	FU, HAIYING

Inventor Search Completed: No Records to Display.

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## Inventor Name Search Result

Your Search was:

Last Name = MUIR

First Name = TIMOTHY



Application#	Patent#	Status	Date Filed	Title	Inventor Name
10807680	Not Issued	30	03/23/2004	Methods of porogen removal for porous low dielectric constant films using plasma treatments	MUIR, TIMOTHY J.

Inventor Search Completed: No Records to Display.

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